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## IAP5 Rec'd PCT/PTO 2 8 MAR 2006

Sheet 1 Form PTO-1449 US Dept. of Commerce ATTY DOCKET NO. APPLICATION NO. PATENT & TRADEMARK OFFICE New U.S. National 127516 (REV. 1/06) Stage of 10/573822 PCT/JP2004/015395 INFORMATION DISCLOSURE STATEMENT (Use several sheets if necessary) **APPLICANTS** Ryoji HOSHI et al. FILING DATE March 28, 2006 U.S. PATENT DOCUMENTS Examiner Cite Document Number Date Name Initials No. 7G.N.R./ US 2002/0017234 A1 02/14/2002 ONO et al. FOREIGN PATENT DOCUMENTS Examiner With Cite With Initials No. Document Number Date Country English English Translation Abstract /G.N.R./ 2. JP-A-07-223893 08/22/1995 **JAPAN** Х /G.N.R./ 3. JP-A-08-157293 06/18/1996 **JAPAN** Х  $\mathbf{X}$ /G.N.R./  $\mathbf{x}$ 02/16/1999 x 4. **JAPAN** JP-A-11-043397 /G.N.R./ JP-A-2002-012498 01/15/2002 **JAPAN** Х Х 5. /G.N.R./ 6. JP-A-2002-226296 08/14/2002 **JAPAN** Х Х /G.N.R./ 7. JP-A-08-330316 12/13/1996 JAPAN X х /G.N.R./ 8. JP-A-11-079889 03/23/1999 JAPAN X х OTHER DOCUMENTS Cite (Including Author, Title, Date, Pertinent Pages, etc.) Examiner Initials No. 9. D.T.J. HURLE et al.; "Mechanism of Swirl Defects Formation in Silicon"; Journal of Crystal Growth; Vol. 59; 1982; /G.N.R./ pp. 625-643. 06/23/2008 **EXAMINER** DATE CONSIDERED /G. Nagesh Rao/ (06/23/2008) 06/23/2008

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and not considered. Include copy of this form with next communication to applicant.

Date: March 28, 2006

Examiner: